



*NSF International Standard /  
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## NSF/ANSI 41 - 2016

Non-liquid Saturated  
Treatment Systems



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Chair, Joint Committee on Wastewater Technology  
c/o NSF International  
789 North Dixboro Road, P.O. Box 130140  
Ann Arbor, Michigan 48113-0140 USA  
Phone: (734) 769-8010 Telex: 753215 NSF INTL  
FAX: (734) 769-0109 E-mail: [info@nsf.org](mailto:info@nsf.org)  
Web: <http://www.nsf.org>

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NSF International Standard/  
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for Wastewater Technology —

**Non-liquid saturated  
treatment systems**

Standard Developer

**NSF International**

**NSF International**

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